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Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp		
L1	2030	703/2.ccls.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/11/14 14:30		
L2	260	L1 and (impur\$4 pileup defects diffusion)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/11/14 14:39		
L3	82	716/19-21 and (impur\$4 pileup defects diffusion)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/11/14 14:39		
L4	724	(716/19-21).ccls. and (impur\$4 pileup defects diffusion)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/11/14 14:39		
L5	79	(716/19-21).ccls. and (impur\$4 pileup)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/11/14 14:39		
L7	341	716/20.ccls.	US-PGPUB; USPAT	OR	OFF	2006/11/14 14:58		
L8	1	716/20.ccls. and (impur\$4 adj pileup)	US-PGPUB; USPAT	OR	OFF	2006/11/14 14:59		
L9	7	(model\$4 with semiconductor with (device process) with impurity).clm.	US-PGPUB; USPAT	OR	OFF	2006/11/14 15:03		
L10	3	(model\$4 with semiconductor with impurity with distance).clm.	US-PGPUB; USPAT	OR	OFF	2006/11/14 15:08		
L11	0	(model\$4 with semiconductor with impurity with lambda).clm.	US-PGPUB; USPAT	OR	OFF	2006/11/14 15:03		
L12	1	"6594625".pn.	US-PGPUB; USPAT			2006/11/14 15:06		
L13	0	(model\$4 with semiconductor with impurity with (gate source drain)). clm.	US-PGPUB; USPAT			2006/11/14 15:08		
L14	4	(US-20010025367-\$).did. or (US-5933359-\$ or US-5737250-\$ or US-5502643-\$).did.	US-PGPUB; USPAT	-		2006/11/14 15:15		
L15	0	(fair with diffusion with model\$4).	US-PGPUB; USPAT	OR	OFF	2006/11/14 15:30		
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Last Name = HAYASHI First Name = HIROKAZU

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stability studies confirm the Importance of Impurity density gradients as a source of free energy (from 5 keV to 30 keV) is recovered by our model for dozens of simulated experiments. Finally, Comparisons of Nonlinear Toroidal Turbulence Simulations with Experiment W. Dorland, M. Comparisons of Nonlinear Toroidal Turbulence.. - Dorland.. w3.pppl.gov/~mbeer/afs/faea_dorland.ps Integrating Feature Construction with Multiple Classiflers... - Vilalta, Rendell (Correct) Is commonly a single feature, selected via some impurity measure, e.g. entropy, gini, Laplace, 2 an important advantage of symbolic learning models over other inductive models (e.g.over a www.research.ibm.com/people/v/vilalta/papers/icml97.ps

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